

**Amendments to the Claims:**

This listing of claims will replace all prior versions, and listings, of claims in the application:

**Listing of Claims:**

1. (Currently Amended) A method for creating a pattern on a substrate, the method comprising the step of:
  - (a) imprinting a first pattern on the substrate; and
  - (b) imprinting a second substantially similar pattern that is intentionally mis-registered in a pre-defined manner with regard to the first pattern so that the combination of the first and second patterns ~~causes a~~ causes continuous, systematic variation in a final size and pre-defined variations in final sizes of defined elements across the substrate consistent with the predefined misregistration so that at least two or more of the defined elements have different dimensions.
2. (Original) The method as in claim 1, wherein step (b) includes providing the elements as structures used for an image sensor.
3. (Original) The method as in claim 2, wherein step (b) includes providing the element as an aperture.
4. (Original) The method as in claim 1, wherein step (b) includes providing the element as a micro-lens.
5. (Original) The method as in claim 1, wherein step (b) includes providing a mask as the substrate, which mask is used as a template for device fabrication.
6. (Original) The method as in claim 1, wherein step (b) includes providing a material upon which the device is fabricated as the substrate.

7. (Original) The method as in claim 3, wherein step (b) includes systematically increasing aperture size as the aperture approaches a periphery of the substrate.

**Discussion Regarding the Drawings:**

Formal drawings are submitted herewith under Separate Letter to the Draftsperson. For the convenience of the Examiner, a copy of the formal drawings are also attached with this amendment.